SENSORS AND ACTUATORS A VOLUME A31, NUMBERS 1–3, MARCH 1992

Contents

Welcome Session

Quo vadis Eurosensors? 1
W. Göpel (Tübingen, FRG)

Applications

Integrated smart two-dimensional thermal flow sensor with Seebeck-voltage-to-frequency conversion 9
J. W. Bosman, J. M. De Bruijn, F. R. Riedijk, B. W. Van Oudheusden and J. H. Huijsing (Delft, Netherlands)

Eddy current sensor for the measurement of a lateral displacement. Applications in the railway domain. 17
P. Aknin (Arcueil, France), D. Placko (Cachan, France) and J.-B. Ayasse (Arcueil, France)

A positioning sensor for tonometric applications. 24
C. den Besten and P. Bergveld (Enschede, Netherlands)

Biaxial scanning mirror activated by bimorph structures for medical applications 29
R. A. Buser, N. F. de Rooij (Neuchâtel, Switzerland), H. Tischhauser, A. Dommann and G. Staufert (Buchs, Switzerland)

How many sensors does a car need? 35
P. Kleinschmidt and F. Schmidt (Munich, FRG)

An optoelectronic sensor for an autonomous mobile robot using passive reflectors. 46
J. P. Simon, M. Betemps and A. Jutard (Villeurbanne, France)

Ultrasonic sensor for reverse driving applications 51
M. Noll, P. M. Knoll and P. Rapps (Ettlingen, FRG)

Mechatronic sensors in integrated vehicle architecture. 54
E. Zabler, F. Heintz, R. Dietz and G. Gerlach (Ettlingen, FRG)

New generation of automotive sensors to fulfil the requirements of fuel economy and emission control 60
J. Binder (Toulouse, France)

A novel non-contact sensor for surface topography measurement using a fibre optic principle 68
C. Butler and G. Gregoriou (Uxbridge, UK)

Final Plenary

Problems associated with bringing a sensor technology to the market place 77
A. J. Collins (Cardiff, UK)

Physical Sensors

Tactile imaging 83
P. P. L. Regtien (Delft, Netherlands)

A subminiature capacitive movement detector using a composite membrane suspension 90
B. Puers and S. Vergote (Heverlee, Belgium)

A stress-component-selective tactile sensor array 97
C. Domenici and D. De Rossi (Pisa, Italy)

An integrated charge amplifier for a smart tactile tensor. 101
M. R. Wolffenbuttel, R. F. Wolffenbuttel and P. P. L. Regtien (Delft, Netherlands)

Intrinsic optical fibre sensor for monitoring acoustic emission. 110
S. X. Zheng, R. McBride, J. S. Barton, J. D. C. Jones (Edinburgh, UK), K. F. Hale and B. E. Jones (Uxbridge, UK)

A capacitive tactile sensor for shear and normal force measurements 115
F. Zhu and J. W. Spronck (Delft, Netherlands)

A smart accelerometer with on-chip electronics fabricated by a commercial CMOS process. 121
W. Riethmüller, W. Benecke, U. Schnakenberg and B. Wagner (Berlin, FRG)

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Calibration systems for strain gauges to be used at cryogenic temperatures 125
C. Ferrero, C. Marinari and E. Martino (Turin, Italy)

Selective detection of organic molecules with polymers and supramolecular compounds: application of capacitance, quartz microbalance and calorimetric transducers 130
K. D. Schierbaum, A. Gerlach, M. Haug and W. Göpel (Tübingen, FRG)

Sensor technology strategy in silicon. 138
P. M. Sarro (Delft, Netherlands)

Design and application of thick-film multisensors 144
N. Hampp, C. Eppelsheim, J. Popp, M. Bisenberger and C. Bräuchle (Munich, FRG)

A new condenser microphone with a p^+ silicon membrane 149
T. Bourouina, S. Spirkovitch, F. Baillieu and C. Vauge (Noisy-Le-Grand, France)

Resonant pressure sensor based on piezoelectric properties of ferroelectric thick films 153
B. Morten, G. De Cicco and M. Prudenziati (Modena, Italy)

The theory of operation of piezoelectric quartz crystal sensors for biochemical application 159
C. Barnes, C. D'Silva, J. P. Jones and T. J. Lewis (Bangor, Gwynedd, UK)

Optically excited silicon sensor for permanently installed downhole pressure monitoring applications 164
T. Kvisterøy, O. H. Gusland, B. Stark (Horten, Norway), H. Nakstad, M. Eriksrud (Trondheim, Norway) and B. Bjørnstad (Oslo, Norway)

Electrical cross-talk in two-port resonators — the resonant silicon beam force sensor 168
C. J. van Mullem, H. A. C. Tilmans, A. J. Mouthaan and J. H. J. Fluitman (Enschede, Netherlands)

A new current sensor using electron spin resonance 174
D. Duret, M. Beranger and M. Moussavi (Grenoble, France)

Non-contacting torque measurement by a modified moiré fringe method 178
R. C. Spooncer, R. Heger and B. E. Jones (Uxbridge, UK)

Ultrasonic echoes from complex surfaces: an application to object recognition 182
J. M. Martín Abreu, T. Freire Bastos and L. Calderón (Madrid, Spain)

Compatibility between bipolar readout electronics and microstructures in silicon 188
K. M. Mahmoud and R. F. Wolffenbuttel (Delft, Netherlands)

Micromachined sensor structures with linear capacitive response. 200
L. Rosengren, J. Söderkvist and L. Smith (Uppsala, Sweden)

Spatial symmetry of transduction effects in Hall plates 206
P. J. A. Munter and D. C. van Duyn (Delft, Netherlands)

Two-dimensional numerical modeling of dual-collector magnetotransistors: evidence for emitter efficiency modulation. 210
C. Riccobene, G. Wachutka, J. Bürgler and H. Baltes (Zurich, Switzerland)

Modelling the pressure and temperature sensitivity of an optically excited micromachined silicon sensor for permanently installed downhole monitoring systems 215
B. S. Douma, P. Eigenraam (Amsterdam, Netherlands) and P. Hatlem (Tananger, Norway)

A magnetic field sensor based on rotating amorphous ribbons 220
V. E. Makhotkin, A. V. Bezrukov, Yu. K. Levin, V. A. Lopatin and B. P. Shurukhin (Moscow, Russia)

Optics and Radiation

Pyroelectric sensor arrays on silicon. 225
W. Ruppel (Karlsruhe, FRG)

Optocoupler based on the avalanche light emission in silicon. 229
B. P. van Drieënhuizen and R. F. Wolffenbuttel (Delft, Netherlands)

An inexpensive real-time 3-D camera with a smart optical sensor. 241
J. Kramer, P. Seitz and H. Baltes (Zurich, Switzerland)

Semiconductor drift detectors for high resolution X-ray spectroscopy. 245
A. Castoldi and M. Sampietro (Milan, Italy)

Spatial resolution of a diffusion-based silicon nuclear radiation detector. 250
S. E. Wouters and T. Otaredian (Delft, Netherlands)

Technology

Integrated grating/detector array fabricated in silicon using micromachining techniques. 259
T. A. Kwa and R. F. Wolffenbuttel (Delft, Netherlands)

Anisotropic crystal etching: a simulation program 267
J. S. Danel and G. Delapierre (Grenoble, France)

Non-equilibrium, irreversibility, non-linearity and instability in the operation of sensors 275
I. Kirschner (Budapest, Hungary) and S. Leppävuori (Oulu, Finland)

KOH etching of high-index crystal planes in silicon 283
E. Herr and H. Baltes (Zurich, Switzerland)

2

1